L Number	Hits	Search Text	DB	Time stamp
1	80	(((resist or photoresist) with round$3) and etch$4) and "ion beam"	USPAT; EPO; JPO; DERWENT; IBM_TDB	2004/05/05 09:58
2	862	((resist or photoresist) with round$3) and etch$4	USPAT; EPO; JPO; DERWENT; IBM_TDB	2004/05/05 09:58
3	81	(MEMS or "micro electromechanical system") and ((pattern$3 or mask$4) with round$3)	USPAT; EPO; JPO; DERWENT; IBM_TDB	2004/05/05 10:02
4	1481	(MEMS or "micro electromechanical system") same (mating or actuator)	USPAT; EPO; JPO; DERWENT; IBM_TDB	2004/05/05 10:03
5	152	(MEMS or "micro electromechanical system") same (mating or actuator) same (pattern$4 or mask$3)	USPAT; EPO; JPO; DERWENT; IBM_TDB	2004/05/05 10:37
6	8	(MEMS or "micro electromechanical system") same (mating) same (pattern$4 or mask$3)	USPAT; EPO; JPO; DERWENT; IBM_TDB	2004/05/05 10:27
12	1		USPAT	2004/05/05 10:32
13	23	(MEMS or "micro electromechanical system") same (mating or actuator) same (slider)	USPAT; EPO; JPO; DERWENT; IBM_TDB	2004/05/05 10:41
14	3	(MEMS or "micro electromechanical system") same (slider) same pattern$4	USPAT; EPO; JPO; DERWENT; IBM_TDB	2004/05/05 10:42
15	175	(MEMS or "micro electromechanical system") and (slider) and pattern$4	USPAT; EPO; JPO; DERWENT; IBM_TDB	2004/05/05 10:43